



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

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Yair ETN-ELI et al

Serial No.: 10/750,969

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Filed: January 5, 2004 Group Art Unit: 1742

For: TEXTURING A
SEMICONDUCTOR MATERIAL
USING NEGATIVE POTENTIAL
DISSOLUTION (NPD) Attorney Docket: 27054

Examiner: Nicholas A. Smith

Mail Stop: Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

ELECTION

Sir:

This is in response to the United States Patent and Trademark Restriction Office Action mailed February 2, 2007, which response is being made on or before March 2, 2007, and for which no extension of time fee is due.

Applicants hereby elect **Group I**, namely Claims 1-92, drawn to a method for texturing a semiconductor material.

Applicants reserve the right to file, at a later date, additional divisional applications claiming priority from the present application which are directed to the non-elected Group.

Respectfully submitted,

A handwritten signature in black ink that appears to read "Martin D. Moynihan".

Martin D. Moynihan
Registration No. 40,338

Date: March 1, 2007